

amorphous structure such as an amorphous silicon germanium film.

BRIEF DESCRIPTION OF THE DRAWINGS

Fig. 1 is a view showing a conventional optical system
5 for forming linear beam;

Figs. 2A, 2B, 2C and 2D are views showing an example of
a pitch of overlapping linear beam when the linear beam is
irradiated by two pulses;

Fig. 3 is a diagram showing absorption coefficients of
10 an amorphous silicon film and a polycrystal silicon film with
respect to wavelength;

Figs. 4A, 4B and 4C are views showing an example of a
method of irradiating linear beam to a large area substrate;

Fig. 5 is a view showing an example of introducing a beam
15 expander to a constitution of Fig. 1;

Fig. 6 is a view showing an optical system for forming
linear beam;

Figs. 7A, 7B, 7C and 7D are sectional views showing steps
of fabricating pixel TFT and TFT of a drive circuit;

20 Figs. 8A, 8B and 8C are sectional views showing steps
of fabricating pixel TFT and TFT of a drive circuit;

Figs. 9A and 9B are sectional views showing steps of
fabricating pixel TFT and TFT of a drive circuit;

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25 Figs. 10A, ~~and~~ 10B ^{and 10C} are sectional views showing steps of
fabricating pixel TFT and TFT of a drive circuit;